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(71) Applicant: **VERSUM MATERIALS US, LLC** [US/US];
8555 South River Parkway, Tempe, Arizona 85284 (US).

(72) Inventors: **TAMBOLI, Dnyanesh**; Versum Materials US,
LLC, 8555 South River Parkway, Tempe, Arizona 85284
(US). **HWANG, Hee Ming**; Versum Materials US, LLC,
8555 South River Parkway, Tempe, Arizona 85284 (US).
YU, Jeong Yun; Versum Materials US, LLC, 8555 South
River Parkway, Tempe, Arizona 85284 (US).

(74) Agent: **YANG, Lina**; Versum Materials US, LLC, 7350
Tilghman Street, Suite 104, Allentown, US 18106-9000
(US).

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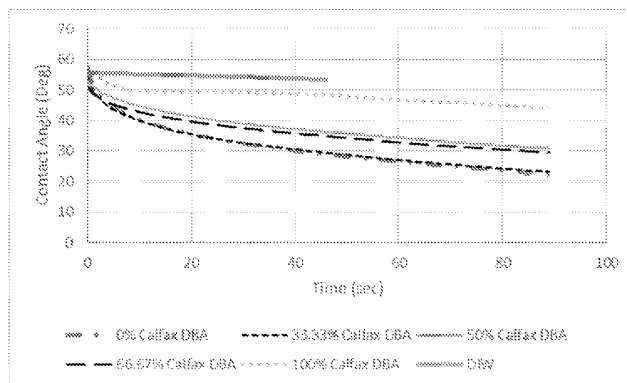


Figure 1

(57) Abstract: The present invention provides a cleaning composition comprises water; one or more organic acid; at least two surfactants wherein the first type surfactant is a diphenyl disulfonic surfactant, the second type surfactant has a surface tension of less than 50 dynes/cm at 0.01wt% concentration in water, and the second type surfactant is not the first type surfactant; and optionally fluoride compounds, polymers, corrosion inhibitors, biological preservatives, pH adjusting agents.

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